
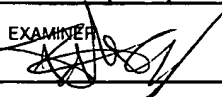

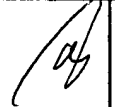
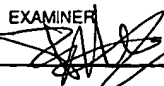
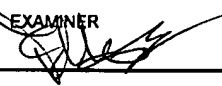


Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-2271	SERIAL NO. 10/664,738	
<div style="text-align: center;">  </div> <p style="text-align: center;">LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p>					APPLICANT: Micron Technology, Inc.		
					FILING DATE September 18, 2003	GROUP 1763	
U.S. PATENT DOCUMENTS							
Examiner's Initials	AA	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
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FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
	AJ						
	AK						
	AL						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
FB	AM	B. Garrido et al., "The Role of Chemical Species in the Passivation of <100> Silicon Surfaces by HF in Water-					
		Ethanol Solutions", J. Electrochem. Soc., Vol. 143, No. 12, December 1996, pp. 4059-4066.					
FB	AN	Wood et al., "Etching Silicon Nitride and Silicon Oxide Using Ethylene Glycol / Hydrofluoric Acid Mixtures",					
		Electrochemical Society Proceedings Volume 99-36, pp. 258-263.					
FB	AO	Knotter et al., "Etching Mechanism of Silicon Nitride in HF-Based Solutions", J. Electrochem. Soc., 148 (3),					
		2001, pp. F43-F46.					
EXAMINER 		DATE CONSIDERED <i>26 May 05</i>					
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>							

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		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
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	AM		T. Kezuka et al., "The Control of Etching Rate for Various SiO ₂ Films", Electrochemical Society Proceedings,				
			Vols. 99-36, 2000, pp. 244-251.				
	AN						
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EXAMINER		DATE CONSIDERED					
		26 May 06					
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>							

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2271		SERIAL NO. Unknown	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Janos Fucsko et al.			
				FILING DATE Filed Herewith		GROUP Unknown	
U.S. PATENT DOCUMENTS							
*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
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FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
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	AK						
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198	AM		Deckert, Pattern Etching of CVD Si ₃ N ₄ /SiO ₂ Composites in HF/Glycerol Mixtures,				
			127 J. ELECTROCHEM. SOC., No. 11, pp. 2433-2438 (November 1980).				
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EXAMINER 		DATE CONSIDERED 26 May 2005					
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